TOUCHSCREEN SERIES C FOR 4” WAFERS

AUTOSAMDRI®-934

RECIPE CAPABLE WITH PROCESS DATA REVIEW

- The New Supercritical Autosamdri®-934 System was developed by our in-house design team whose goal was to listen to and incorporate your needs into our next generation.

- The classic features you have come to expect for decades that enable smooth operation, precise control and reproducibility are again evident in our most current design!

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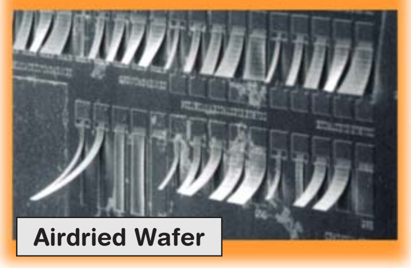
Autosamdri®-934

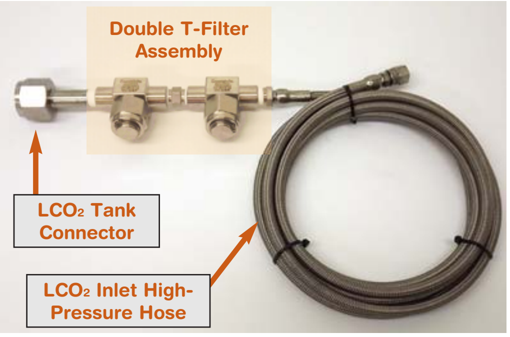
Catalog# 8788A *(Process Various Wafer Sizes up to 4in)*

- ***Process up to Five 4” Wafers per Process Run***
- ***Touchscreen Programmable Interface***
- ***First Time Ever...Previous Run Data Review***
- ***Integrated Chiller Loop Decreases LCO$_2$ Consumption***
- ***Easy Facilitation with Small Foot Print Design***



FEATURES

- A dedicated initial Slow Fill into the process chamber allows ideal fluid dynamics preserving the most sensitive micro devices.
- Maintenance made easy via accessible components including the external Post-Purge-Filter assembly.
- Patent Pending "Vortex Swirl": Non-mechanical stirring chamber allowing for fluid dynamic exchange without the need for particle generating friction causing devices.*
- Extremely Efficient integrated Closed Cooling Loop dropping chamber temperature quickly for shorter process run times.*
- The internal SOTER(tm) condenser* quietly captures and separates CO$_2$ exhaust and waste alcohols.
- Our original Chamber Inserts enable chamber I.D. variance of chamber I.D. maximizing efficiency in LCO$_2$ consumption, process time, and providing multiple size wafer process capability!
- Process chamber LCO$_2$ filtration down to 0.08µm with 99.999%+ particle retention.
- Processes up to five 4" wafers each run. Included are the following HF Compatible Wafer Holders: 4", 3", 2" and 10mm Die Holders.
- Chamber Illumination via viewing window facilitates chamber status visualization.*
- Automatic process with factory default recipe or the ability to customize your own!*
- All internal surfaces are inert to CO$_2$ and ultrapure alcohols.
- Repeatable operating parameters insuring “reproducibility” of results.
- Safety operation features integrated into both temperature and pressure automatic regulation.
- All electronic components meet CE, UL and/or U.S. Military Specifications.
- Clean room static-free compatible design.



Standard Accessories

SPECIFICATIONS

- Cabinet: 19.8" (50.3cm) Width x 31.7" (80.6cm) Depth x 44.5" (113.0cm) Height
- System Set-Up Area Footprint: 27” (68.6cm) Width x 38” (96.5cm) Depth
- Chamber size: 4.50” I.D. x 1.25” Depth / Chamber volume: 326 ml
- 120V or 220V / 50-60Hz
- LCO$_2$ flow is precisely controlled through Micro Metering Valves with Vernier handles for adjustment ease.*

STANDARD ACCESSORIES

- High Pressure LCO$_2$ flexi-SS316 Braided line for safe operation and easy installation 10ft/3m length included with system. (Other lengths available upon request up to 100 ft/30m)
- Double T-Filter Assembly (#8785) pre-installed onto the chamber LCO$_2$ supply high-pressure hose.
- Static free exhaust tubing included for all exhaust ports.
- Spare chamber O-rings (3), chamber lamps (2), and slo-blow fuses (2x3A and 2x8A).
- Chamber Inserts included: 4" to 3" / 3" to 2" / 2" to 1.25" ! Allows for multiple wafer size drying.
- HF compatible wafer holders included: 4", 3", 2" and 10mm square die. Each holder can load up to five substrates each.
- 2 year warranty on all parts and labor.
- Free lifetime technical support.

Note: *Actual delivered model or accessories may vary slightly, as advancements are being constantly applied.*

* Most Autosamdri® feature U.S. patents (#6,493,964, #6,678,968) or patents pending.

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